

WHAT IS CLAIMED IS:

1. A method of dressing a polishing cloth by bringing a dresser in contact with the polishing cloth, comprising:

measuring the height of a surface of the polishing cloth at radial positions of the polishing cloth in a radial direction thereof; and

maintaining a dressing condition while the removal thickness of material from the polishing cloth is in an allowable range.

2. A method according to claim 1, wherein the dressing condition is the rotational speed of the dresser.

3. A method of dressing a polishing cloth by bringing a dresser in contact with the polishing cloth, comprising:

measuring the height of a surface of the polishing cloth at radial positions of the polishing cloth in a radial direction thereof; and

increasing a rotational speed of the dresser if the surface of the polishing cloth is higher at the inner circumferential region than at the outer circumferential region.

4. A method of dressing a polishing cloth by bringing a dresser in contact with the polishing cloth, comprising:

measuring the height of a surface of the polishing cloth at radial positions of the polishing cloth in a radial direction thereof; and

lowering a rotational speed of the dresser if the surface of the polishing cloth is higher at the outer circumferential region than at the inner circumferential region.

5. A method of dressing a polishing cloth by bringing a dresser in contact with the polishing cloth mounted on a turntable, comprising:

measuring the height of a surface of the polishing cloth at radial positions of the polishing

cloth in a radial direction thereof; and

increasing a ratio of a rotational speed of the turntable to a rotational speed of the dresser if the surface of the polishing cloth is higher at the inner circumferential region than at the outer circumferential region.

6. A method of dressing a polishing cloth by bringing a dresser in contact with the polishing cloth mounted on a turntable, comprising:

measuring the height of a surface of the polishing cloth at radial positions of the polishing cloth in a radial direction thereof; and

lowering a ratio of a rotational speed of the turntable to a rotational speed of the dresser if the surface of the polishing cloth is higher at the outer circumferential region than at the inner circumferential region.

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